



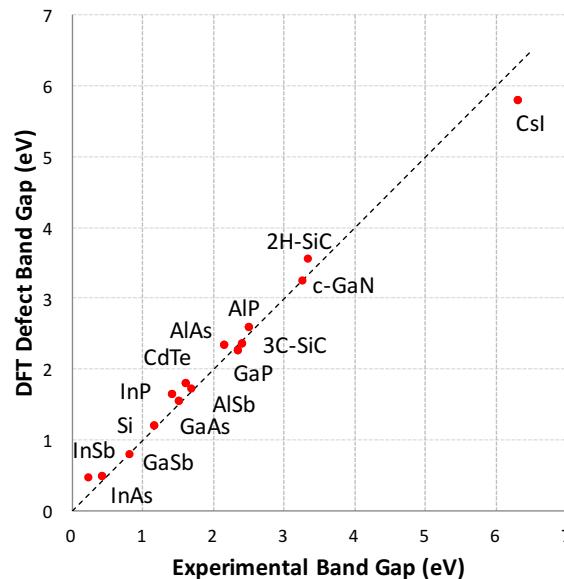
From narrow gap to ultra-wide band gap systems: End of band gap problem excuses for defect calculations

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MRS Fall Meeting 2017

Why model defects in semiconductors and insulators?

Radiation effects in electronics

Process modeling for semiconductors

Defect chemistry for energy applications

Goals:

(1) Qualitative understanding - *Forensics*

Augment experiments

- incomplete, inconclusive, unavailable, expensive

(2) Quantitative characterization - *Predictive*

Predictive simulations, inform coarser models

- not just publishable, but defensible to engineers

The DFT defect shibboleths

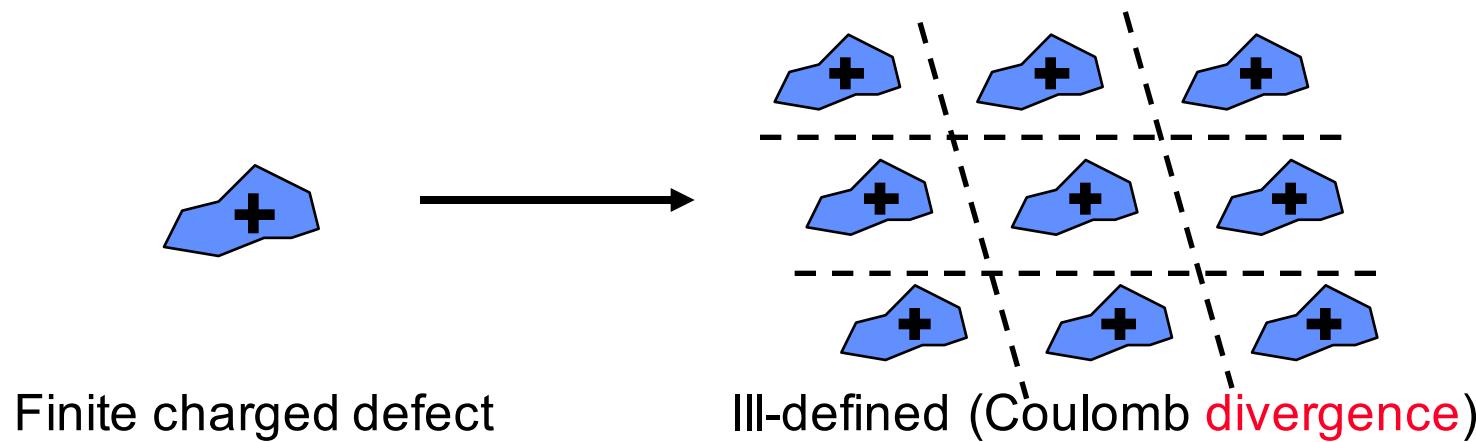
- **“If you do not have the right band gap, you cannot hope to get the defect levels right”**
- **If you have the right band gap, you will get accurate defect levels**

By the end of this talk ...

- the Kohn-Sham gap mostly irrelevant to defect levels
- boundary-conditions/finite-size-errors matter more
- accuracy *proven* with standard semi-local functionals

Challenges for density functional theory

- **Conventional DFT fails for defect levels in semiconductors**
 - (1) Physical accuracy: e.g., “band gap problem”
 - (2) Computational model size limitations
 - (3) Shortage of good data for validation
 - (4) Supercell problem for charged defects:



Lots of DFT calculations, no robust, predictive method

A supercell theory of defect energies

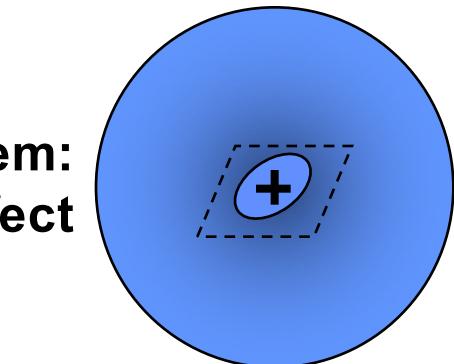
Peter A. Schultz, Phys. Rev. Lett. **96**, 246401 (2006).

Target system:
isolated defect

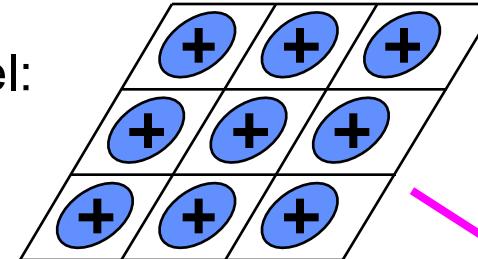
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Computational
model for
isolated defect

(+ DDO
for defect
banding)

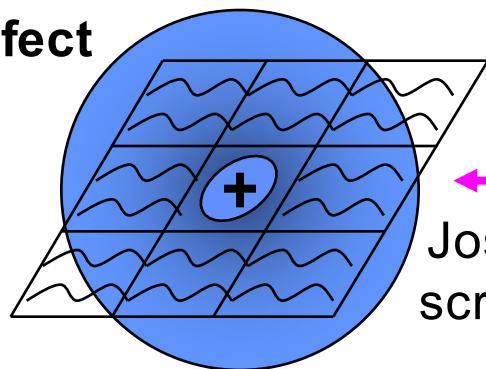


Standard
DFT model:
Supercell

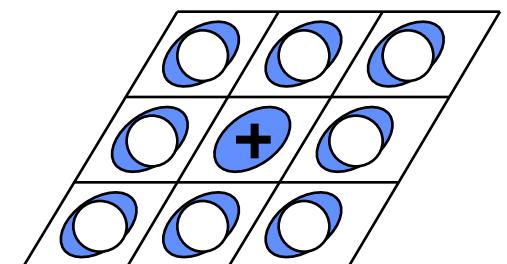


LMCC to fix
boundary
conditions

Finite Defect Supercell Model



Jost Bulk
screening



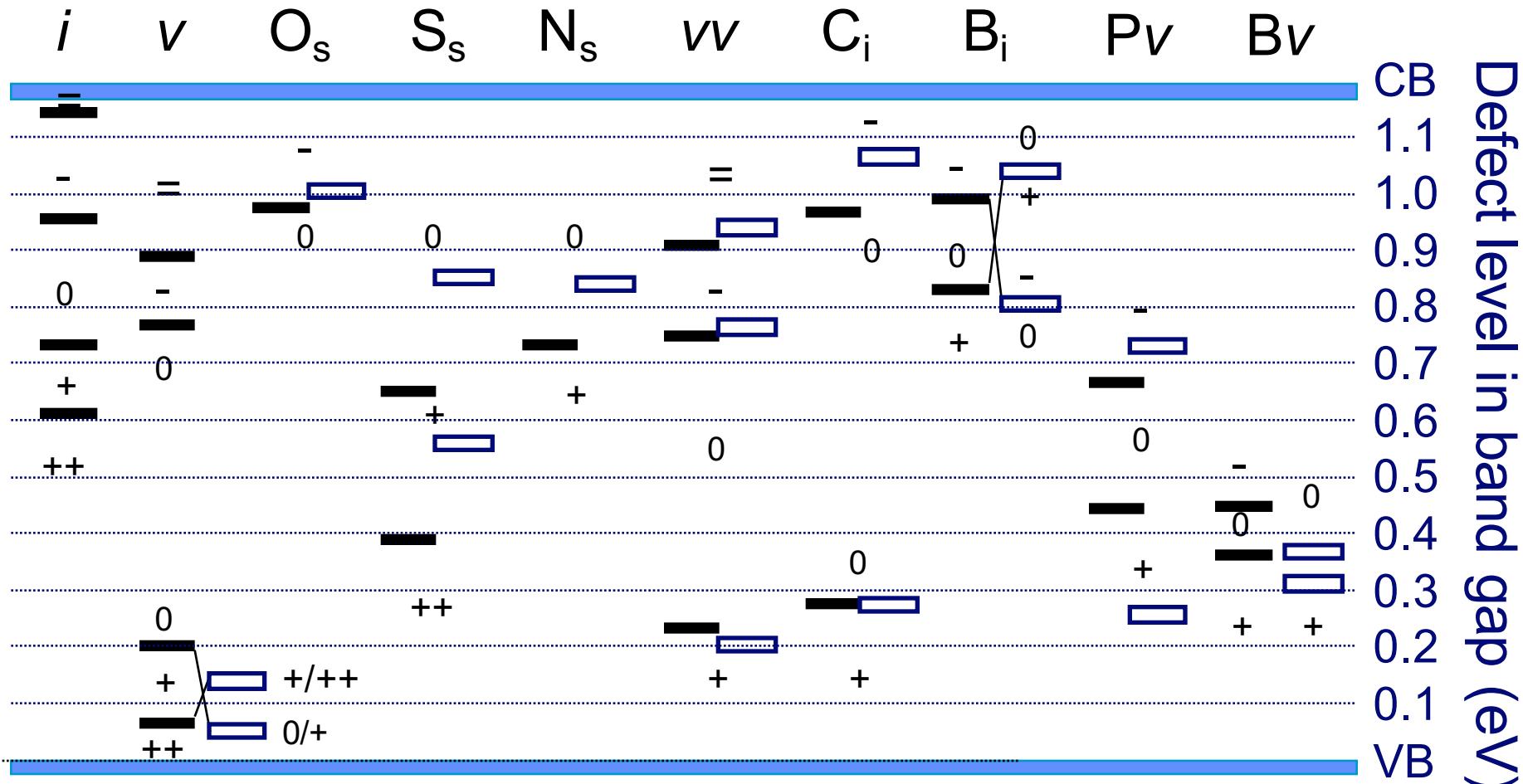
Crystal embedding
to fix μ_e

*“Ab initio” computational model – connect model to physics
Calculations with rigorous control of charge boundary conditions*

(i.e., not jellium-based)

Si: DFT/LDA vs. Experimental Levels

Peter A. Schultz, Phys. Rev. Lett. **96**, 246401 (2006).



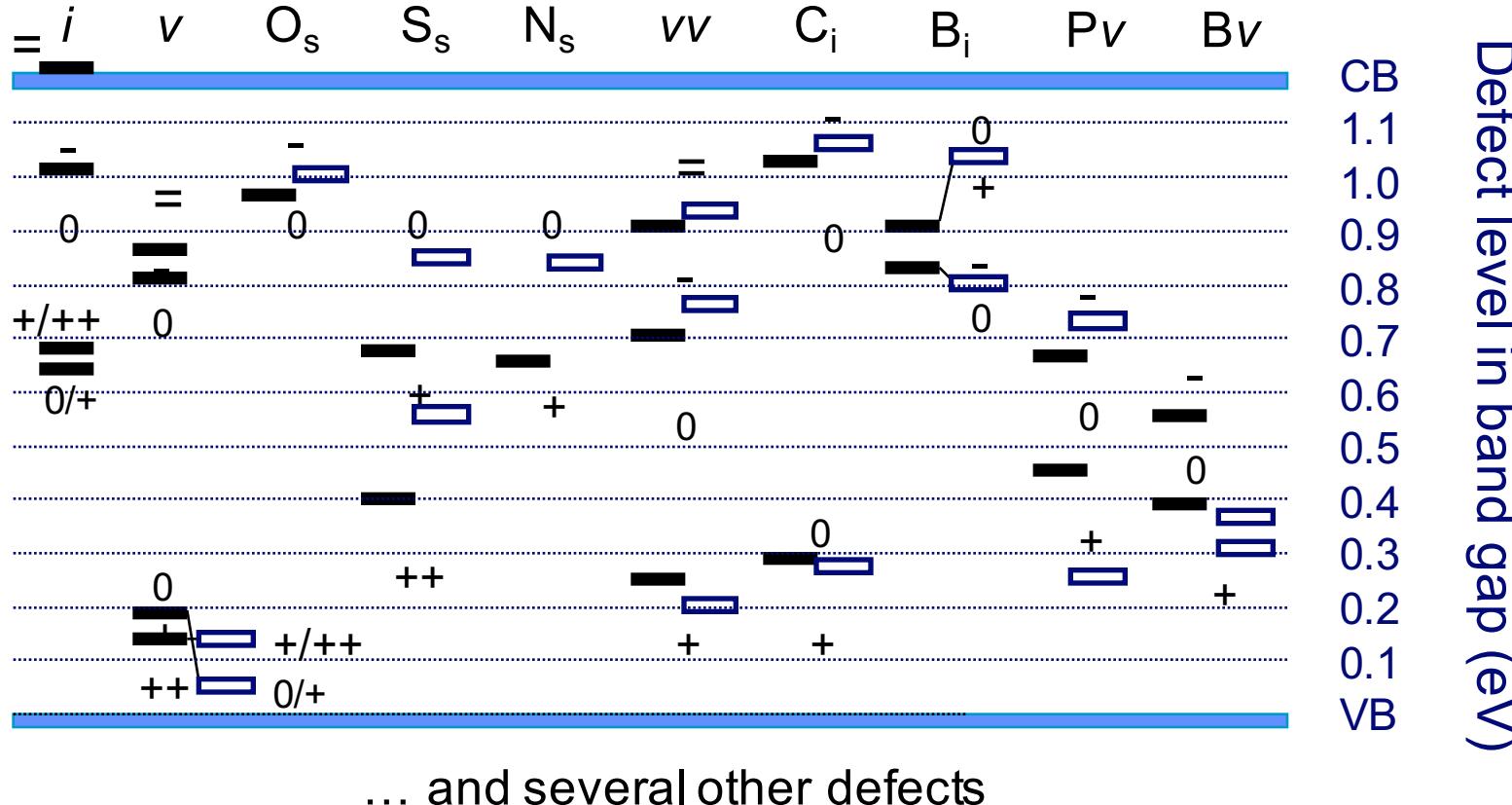
LDA: max error=0.25 eV, mean |error|= 0.10 eV

Intrinsic, first-row, second-row, and complexes across gap

LDA Kohn-Sham gap is only 0.5 eV

Si: DFT/PBE vs. Experimental Levels

P.A. Schultz and A.H. Edwards, NIMB 327, 2-8 (2014).



DFT/PBE defect level max $|error|=0.20$ eV, mean $|error|=0.10$ eV
 DFT “defect gap” matches experiment (KS gap: 0.6 eV)

Absence of validated HSE/hybrid functional results

Computational methods – III-V's

- General purpose DFT code SeqQuest (<http://dft.sandia.gov/Quest>)
 - well-converged (contracted-Gaussian) local orbital basis
 - both LDA and PBE functionals
 - converged norm-conserving pseudopotentials (Ga,In both $Z_{\text{val}}=3,13$)
 - full force relaxed (<1 meV total energies)
 - full FDSM ... robust control of boundary conditions
- Large bulk simulation supercells
 - $a_0=a_0(\text{theory})$; GaAs: 5.60Å(LDA), 5.63Å(3d), 5.74Å(PBE); $a_0(\text{expt})=5.65$ Å
 - Up to 1000-atom supercells; cubic: 64-, 216-, 512-, 1000-site
 - k -sampling: 3^3 for 64-site cells, 2^3 for larger (up to 1000-site) supercells,
 - explicit bulk screening
 - all these computational parameters are **tested** for convergence

Comparable to methods that yielded 0.1 eV accuracy in Si

Simple intrinsic defects in GaAs: LDA

P.A. Schultz and O.A. von Lilienfeld, MSMSE 17, 084007 (Dec. 2009).

$216^- = 512^- = 1000$ -site

Verification: cell-converged

LDA-3d = LDA to ≤ 0.1 eV

Verification: PP converged

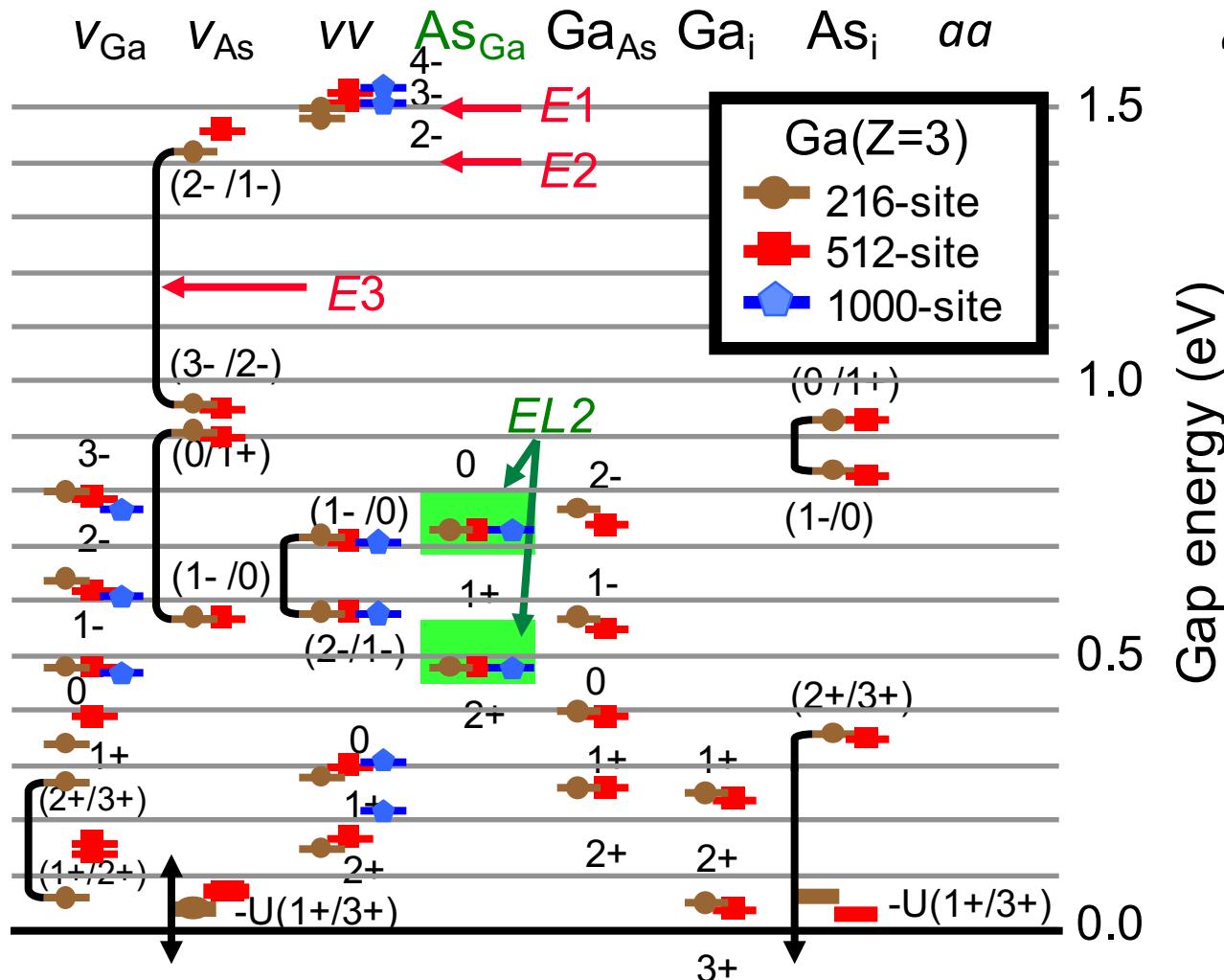
LDA~PBE; spin < 0.05 eV

Verification: functionals

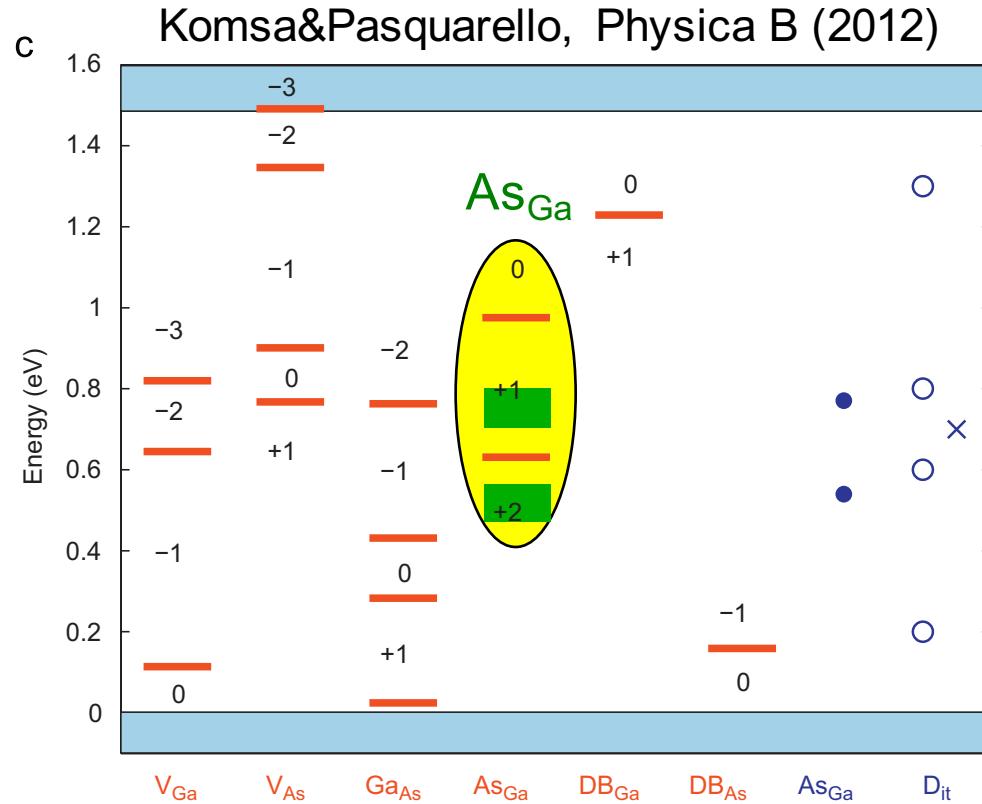
As_{Ga} levels = $EL2$ levels

v_{Ga} levels below midgap

Validation: levels < 0.1 eV



HSE for GaAs defects?



HSE gives **worse** results for EL2/ As_{Ga}

(but: huge HSE computational cost ... small cell, large-core PP)

$E1-E2$ radiation center is the GaAs divacancy

P.A. Schultz, J. Phys.: Condens. Matter **27**, 075801 (2015).

Old (experimental) lore, back to 1988:

$E1, E2$ center = $v_{As}(-/0)$, $v_{As}(0/+)$

$E3 = v_{As} + i$

vv is dismissed

Level structure reassigned with DFT:

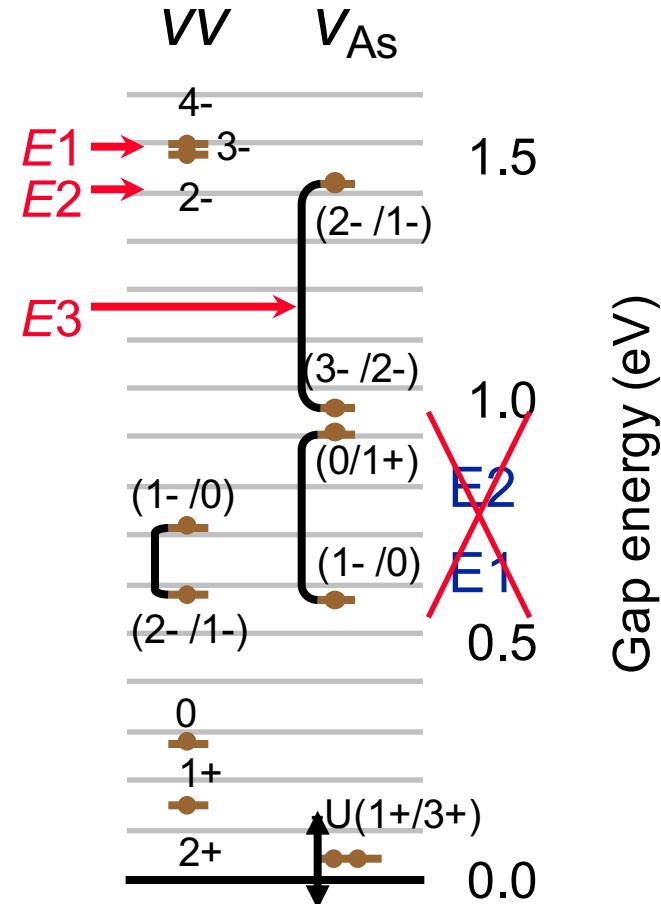
$v_{As}(-/+)$ is mid-gap negative-U (only *one* level)

$v_{As}(3-/1-)$ is upper-gap -U (one level)

$vv(4-/3-/2-)$ near conduction band

vv is major radiation defect: $E1-E2$

$v_{As}(3-/1-)$ transition is the $E3$

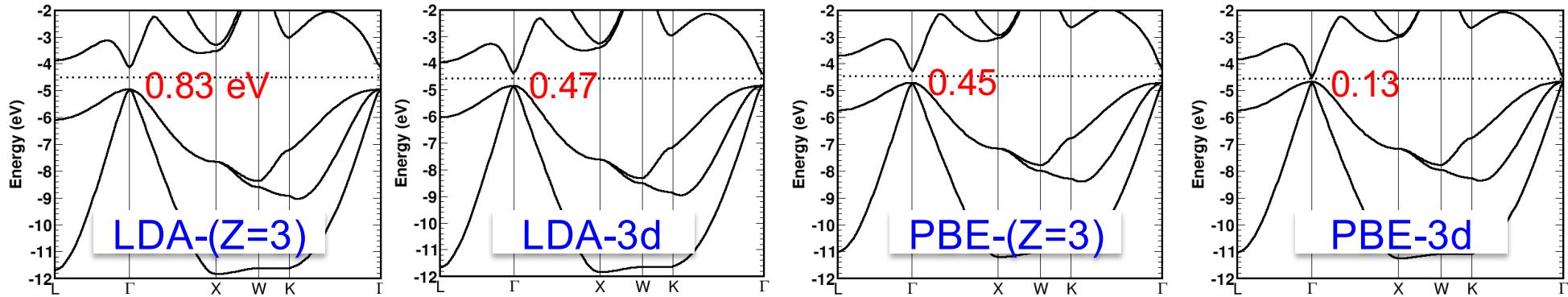


DFT-SeqQuest+FDSTM levels good enough to identify defects based on ***quantitative*** defect level calculations

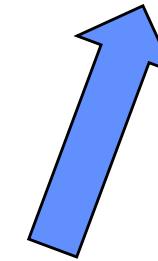
GaAs: A theoretical band gap laboratory

P.A. Schultz and A.H. Edwards, NIMB 327, 2-8 (2014).

Change the Ga pseudopotential and the functional, and the **KS band gap shrinks...**



from 0.83 eV, LDA, Ga($Z=3$) pseudopotential (PP) ...

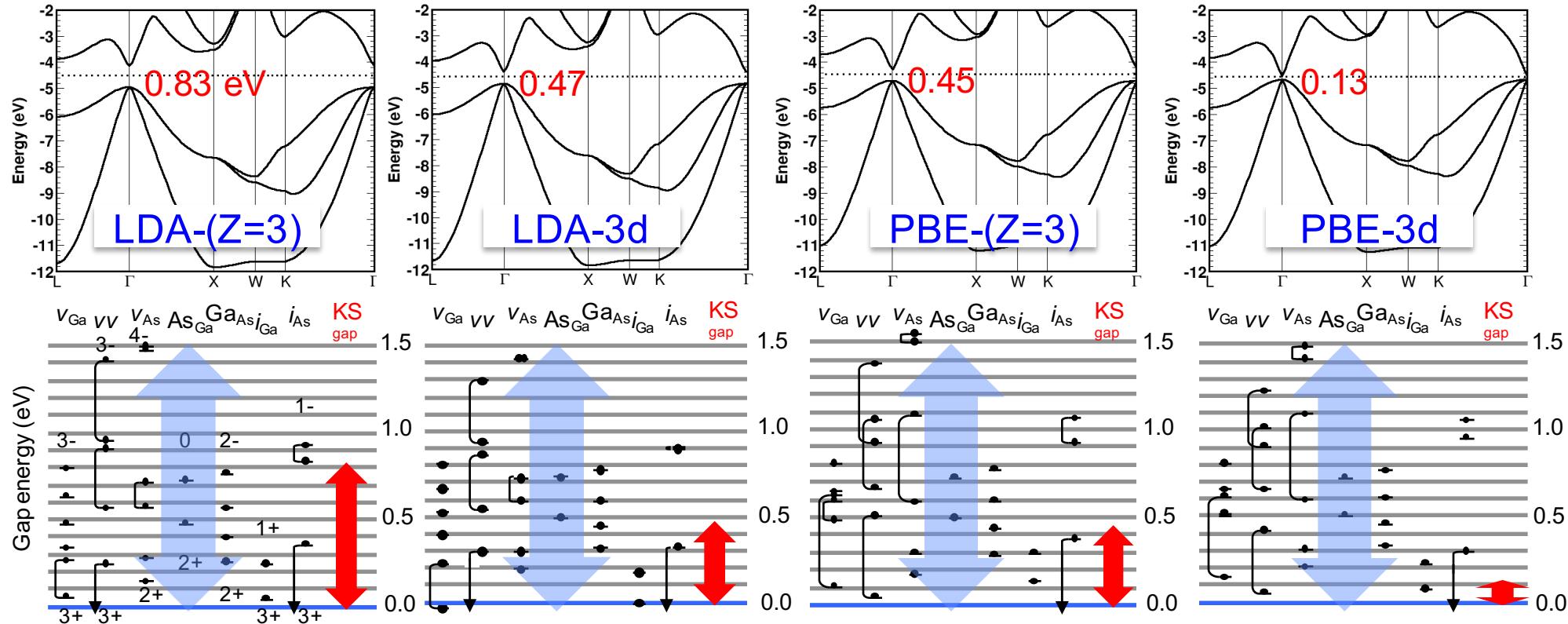


... to 0.13 eV, PBE-3d, Ga($Z=13$) pseudopotential (PP)

GaAs: A theoretical laboratory

P.A. Schultz and A.H. Edwards, NIMB 327, 2-8 (2014).

Change the Ga pseudopotential and the functional, and the KS band gap changes ...



... but span of (total-energy-based) defect levels, the “defect band gap”, does not

Defect levels/gap *insensitive* to size of Kohn-Sham gap!

The DFT “Defect band gap”

- Kohn-Sham gap: *outside* bounds of VB to CB *band eigenvalues*
- Defect band gap: *inside* bounds of transition *energies* for defect levels

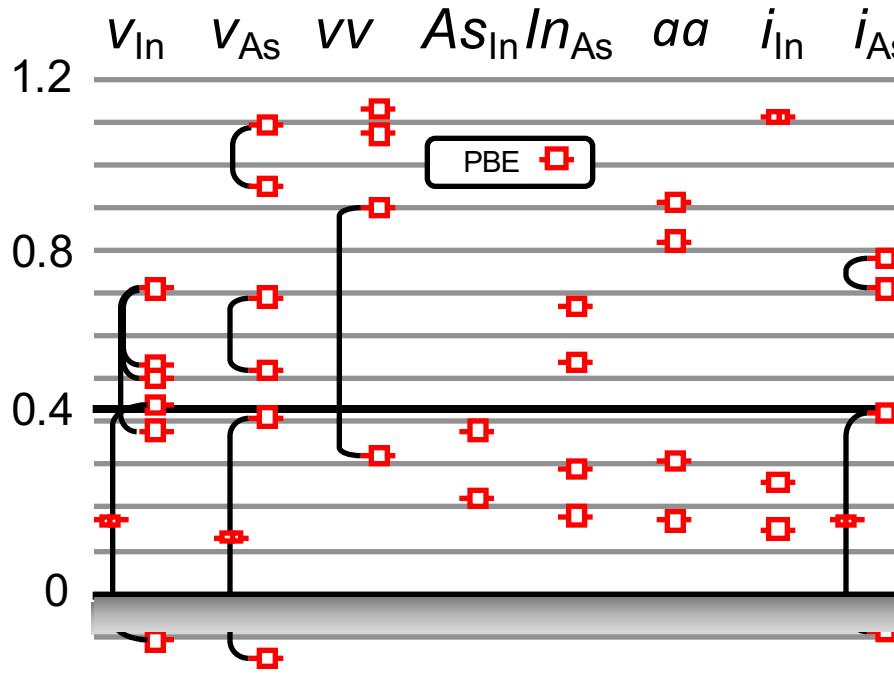
Band gaps: experiment, Kohn-Sham, DFT defect gap

Si	1.17 eV		AlAs	2.16 ⁱ eV		AIP	2.51 eV	
	KS	Defect		KS	Defect		KS	Defect
lda	0.49	1.2	lda	1.37	2.3	lda	1.48	2.55
pbe	0.62	1.2	pbe	1.53	2.3	pbe	1.67	2.55
	1.52 eV		GaP	2.35 ⁱ eV		InP	1.42 eV	
	KS	Defect		KS	Defect		KS	Defect
lda	0.83	1.54	lda	1.51	2.35	lda	0.67	1.7
lda-3d	0.47	1.52	lda-3d	1.47	2.35	lda-3d	0.66	1.7
pbe	0.45	1.50	pbe	1.74	2.35	pbe	0.47	1.7
pbe-3d	0.13	1.50	pbe-3d	1.52	n/c	pbe-3d	0.46	n/c

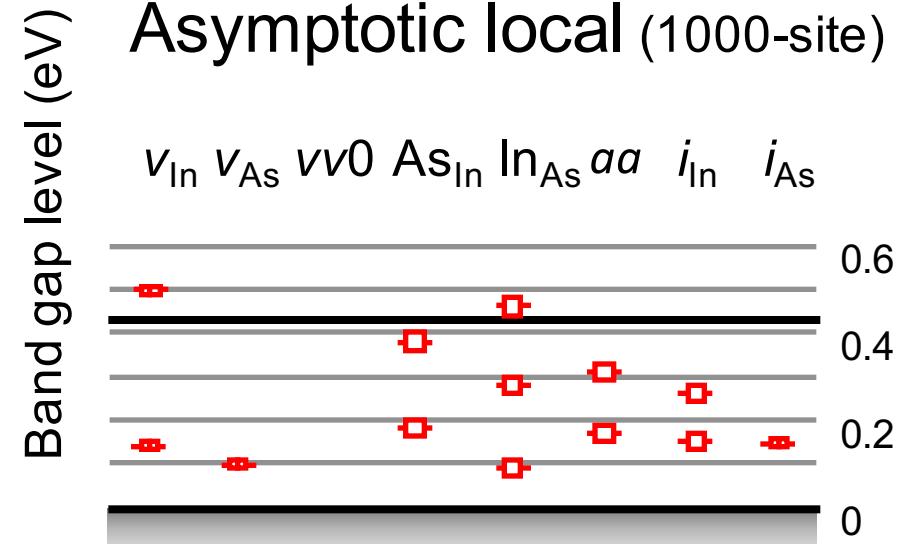
Defect band gap matches (overshoots?) experiment

InAs – no KS-DFT gap, no defects?

“Small” cell (216-site)



Asymptotic local (1000-site)

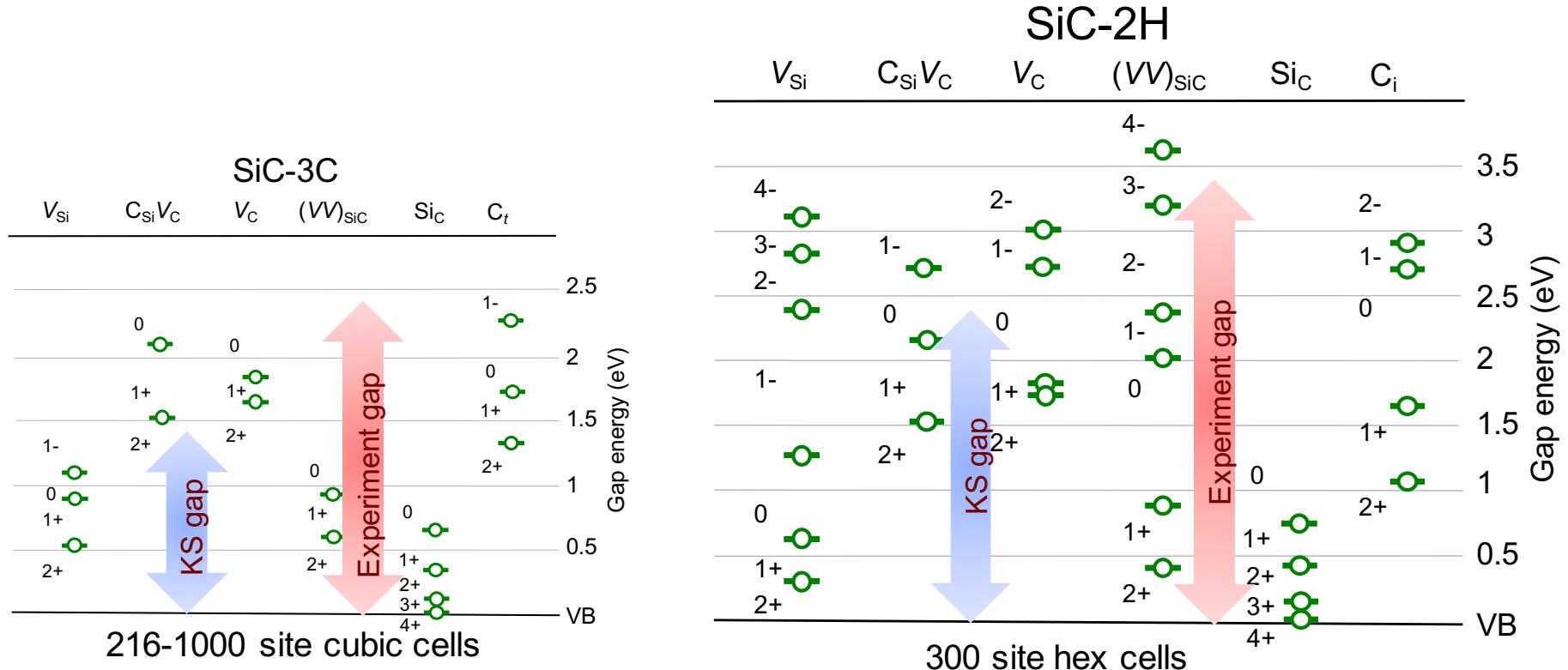


Too many defects!

Need **1000-site** supercells to discriminate localized defects

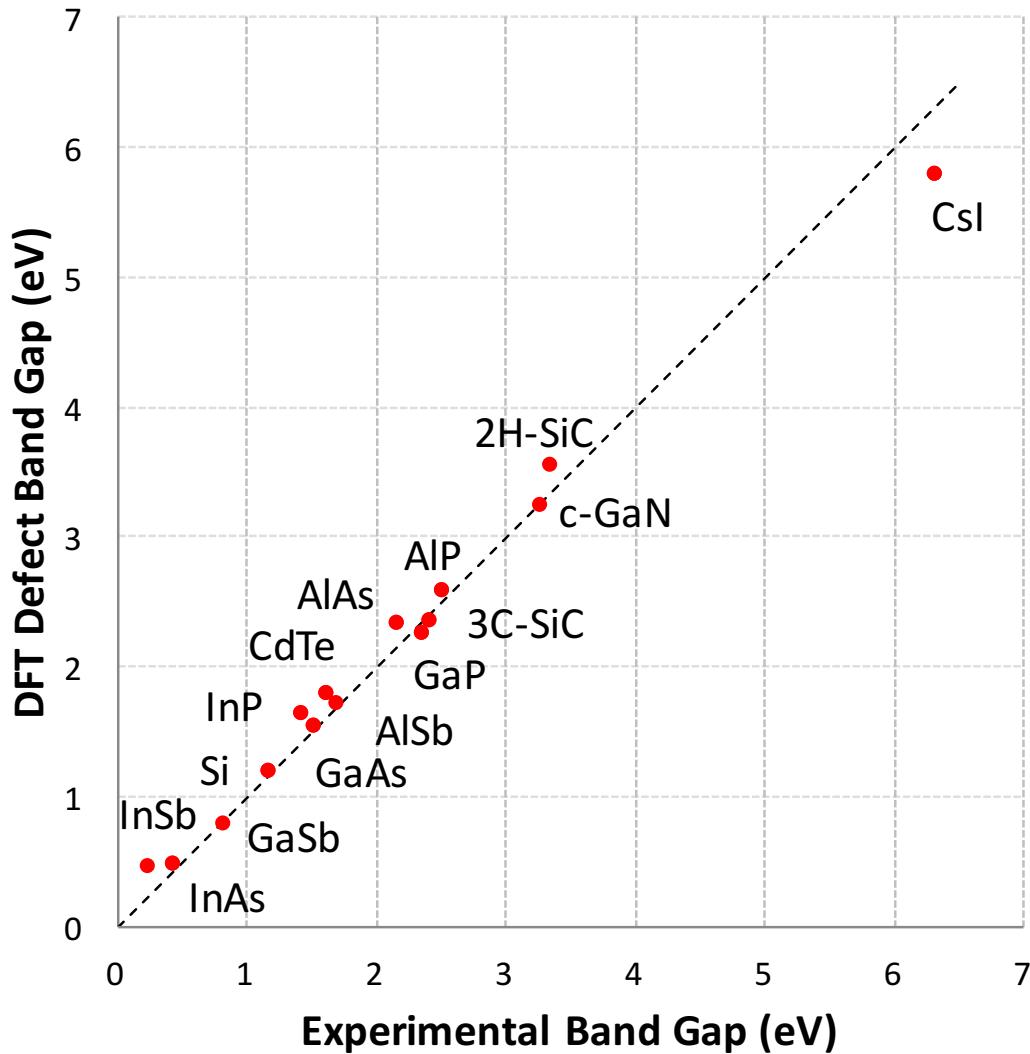
Need to resolve finite-size errors near band edges

SiC – polymorphs



Total-energy-based defect levels
Predicts correct defect band gap for 3C-SiC and 2H-SiC

The PBE Defect Gap vs. the Band Gap



PBE defect gap = experiment, *despite a band gap problem*

Conclusions

- “If you do not have the right band gap, you cannot hope to get the defect levels right” ?
- Defect band gap predicts experimental band gap, despite KS-DFT band gap error
- Insensitive to change in functional (LDA vs. PBE), or pseudopotential
- Varied KS-DFT gap (GaAs “laboratory”) → no change in levels or defect gap
- Zero KS-DFT band gap (InSb, InAs, GaSb) → good defect band gap
- Insensitive to k-sample gap (Si k-sample gap = KS gap)
- Semilocal DFT+FDSTM - quantitative (~0.1 eV) for defect levels (where HSE fails)
→ importance of boundary conditions and finite size (supercell) effects

----- Supporting slides -----

CsI defect level spectrum - DFT

R. M. Van Ginhoven and P.A. Schultz, J.Phys.: Cond. Matter **25**, 495504 (2013)

250-site results = 432-,686-site

Verification: cell-converged

v_1 levels match experiment

Validation of accuracy

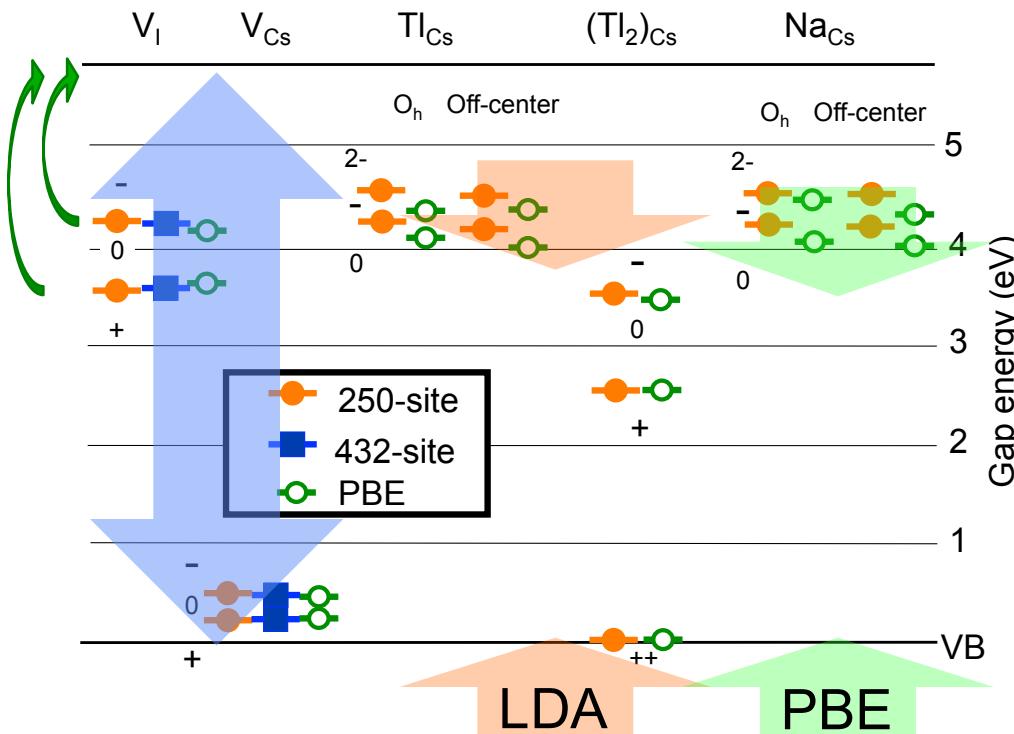
CsI band gap

KS-LDA: 3.80 eV

KS-PBE: 3.58

Defect span: >5.8 eV

Experiment: 6.3 eV

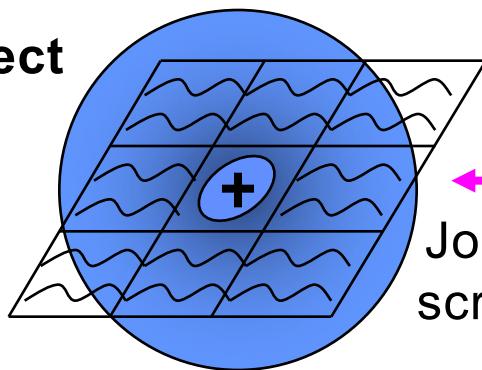


Not a band **gap** problem, a **band edge problem**—
where are they cf. total energy defect levels?

A supercell theory of defect energies

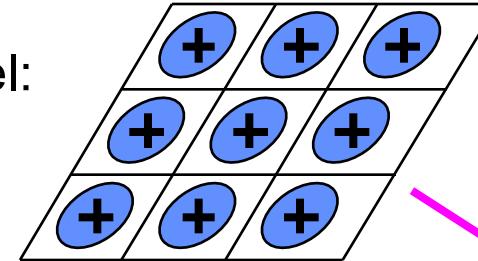
Peter A. Schultz, Phys. Rev. Lett. **96**, 246401 (2006).

Target system:
isolated defect
=
Computational
model for
isolated defect



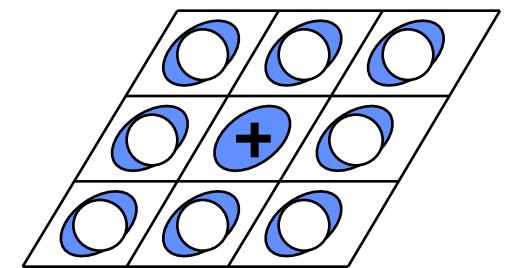
(+ DDO
for defect
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Standard
DFT model:
Supercell

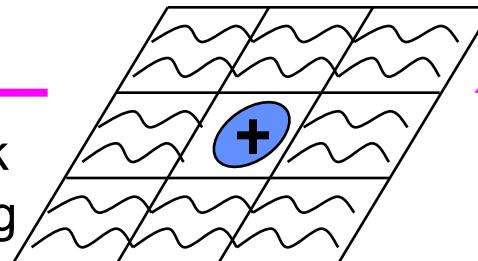


Finite Defect Supercell Model

LMCC to fix
boundary
conditions



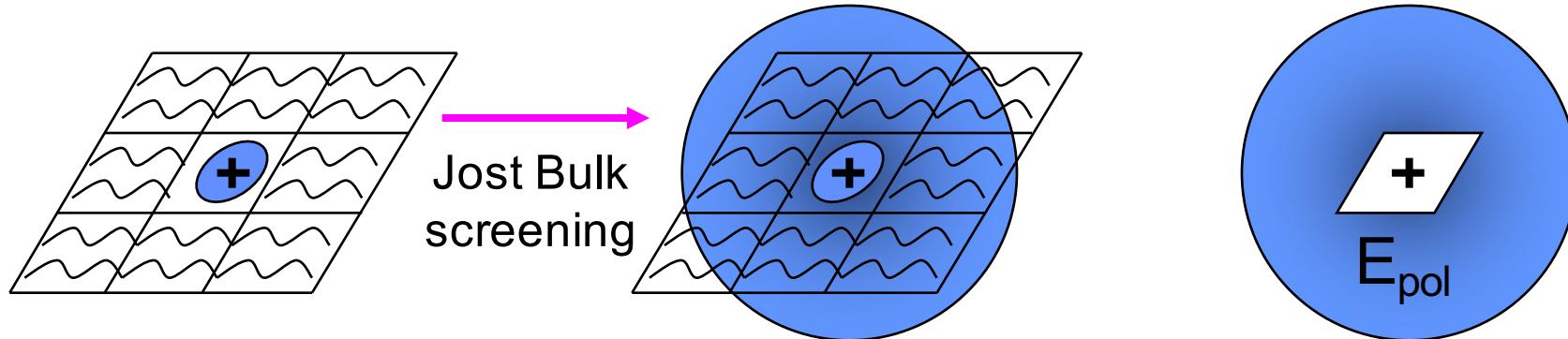
Jost Bulk
screening



Crystal embedding
to fix μ_e

FDSM: *Ab initio* computational model – connect model to physics
Calculations with rigorous control of charge boundary conditions

The polarization model



For extrapolation to bulk, need energy of screening outside of supercell: E_{pol}

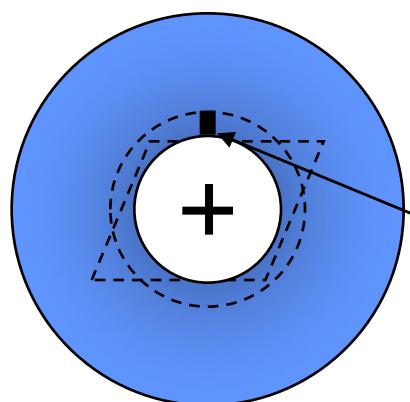
Jost model: $E_{\text{pol}} = \frac{(1 - 1/\epsilon_0) q^2}{R_{\text{jost}}}$

$$R_{\text{jost}} = R_{\text{vol}} - R_{\text{skin}}$$

q = charge on defect

$$R_{\text{jost}} = R_{\text{vol}} - R_{\text{skin}}$$

R_{vol} = radius of volume sphere



Two parameters for any material

R_{skin} = unscreened volume **inside** cell.
fit: = 1.3-1.7 Bohr

ϵ_0 = static dielectric constant - expt
Si GaAs InP GaP AlAs InAs
11.8 13 12.5 11.2 10.1 15.15